

FIG. 1A

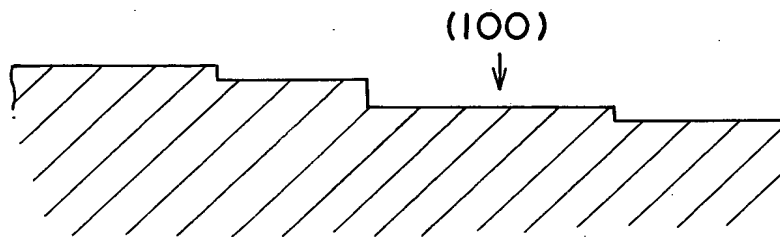


FIG. 1B

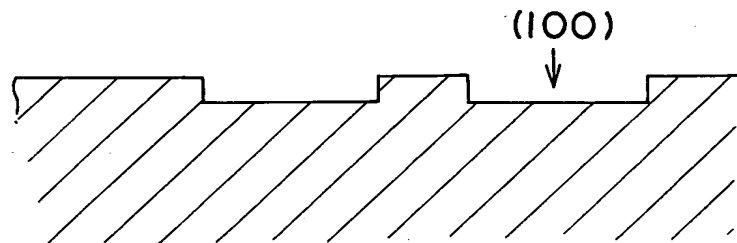


FIG. 1C

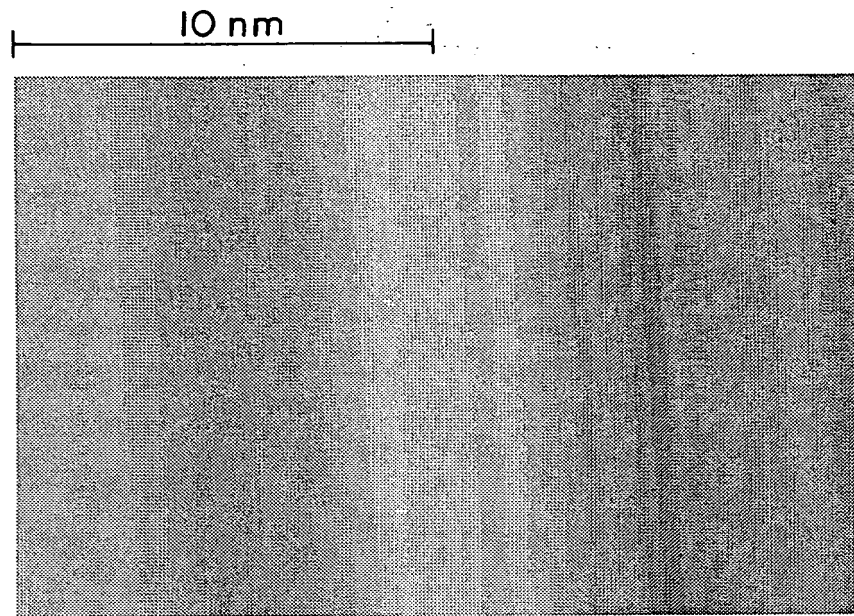


FIG. 2A

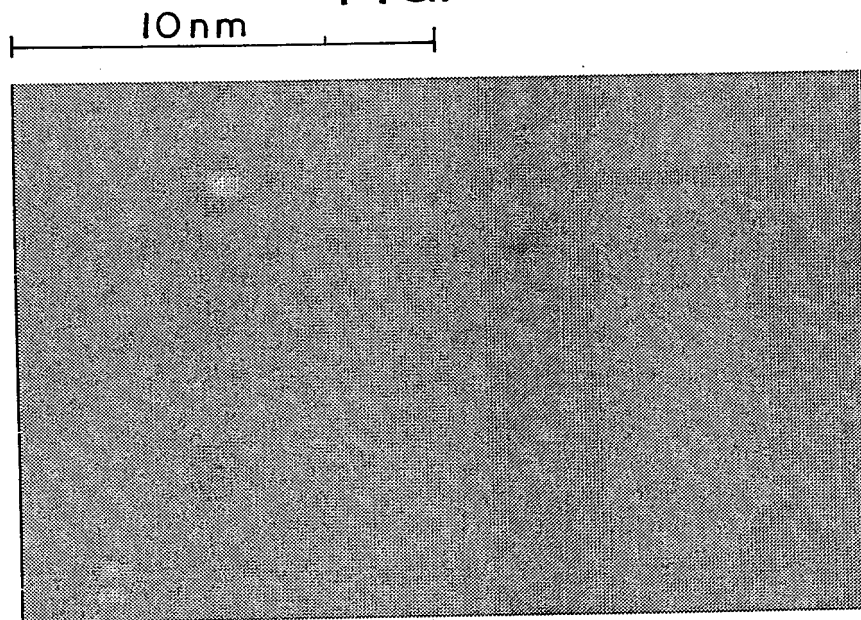


FIG. 2B

09/926188 09/2001

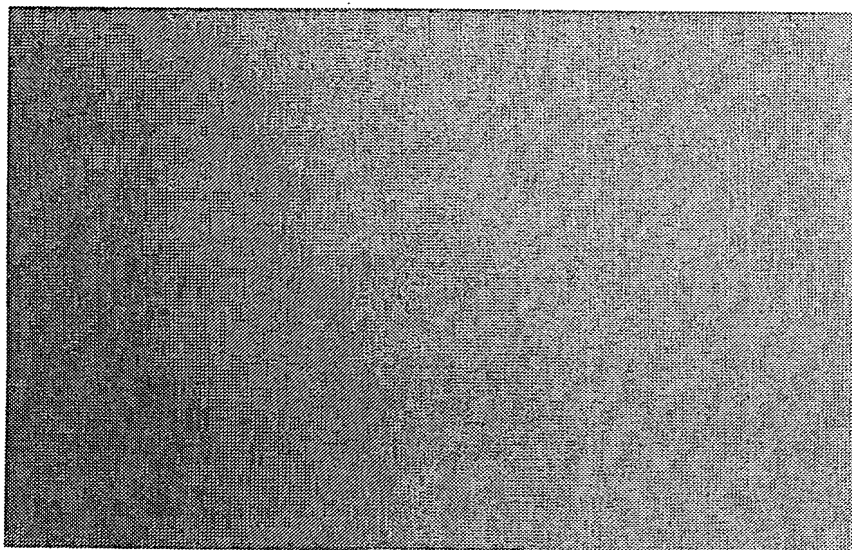
10 μ m

FIG. 3A

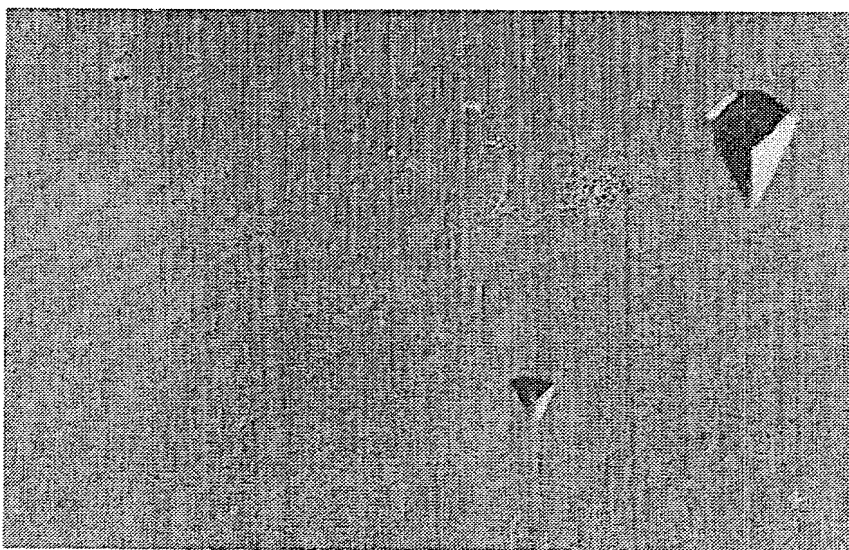
10 μ m

FIG. 3B

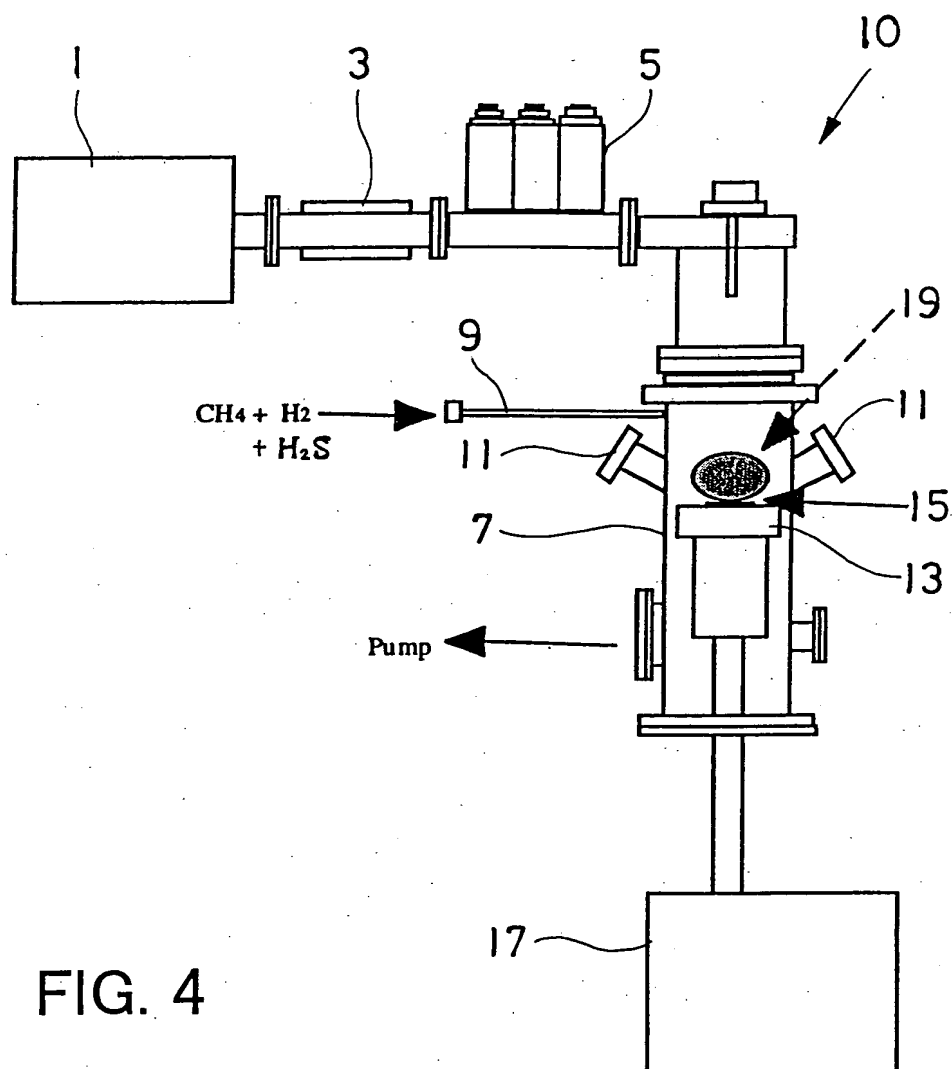


FIG. 4

Gas source	CH ₄ /H ₂ S/H ₂
CH ₄ Concentration	1. 0%
H ₂ S Concentration	10~100 ppm
S/C Ratio	1000~10000 ppm
Total gas flow rate	200 ml min ⁻¹
Gas pressure	40 Torr
Microwave	2. 45 GHz, 300~400 W
Substrate temperature	830°C
Diamond substrate	HP-HT Ib Diamond (100)

FIG. 5

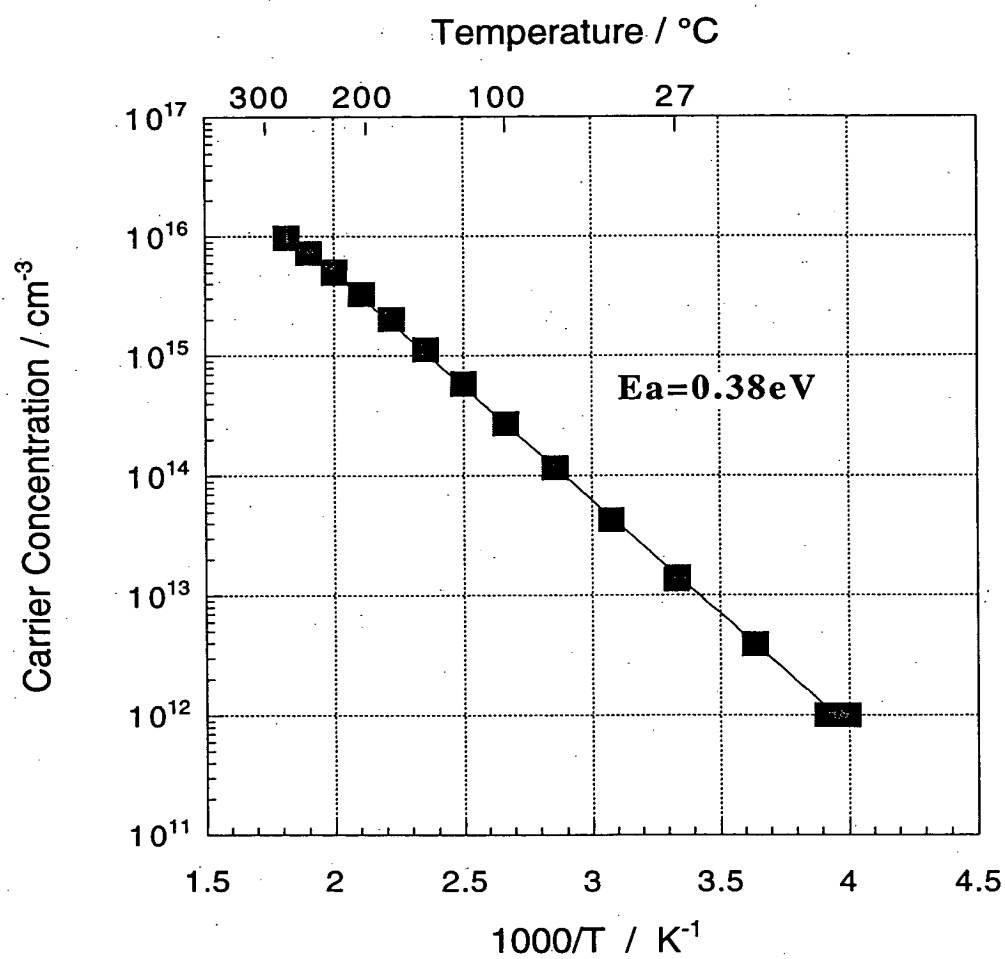


FIG. 6

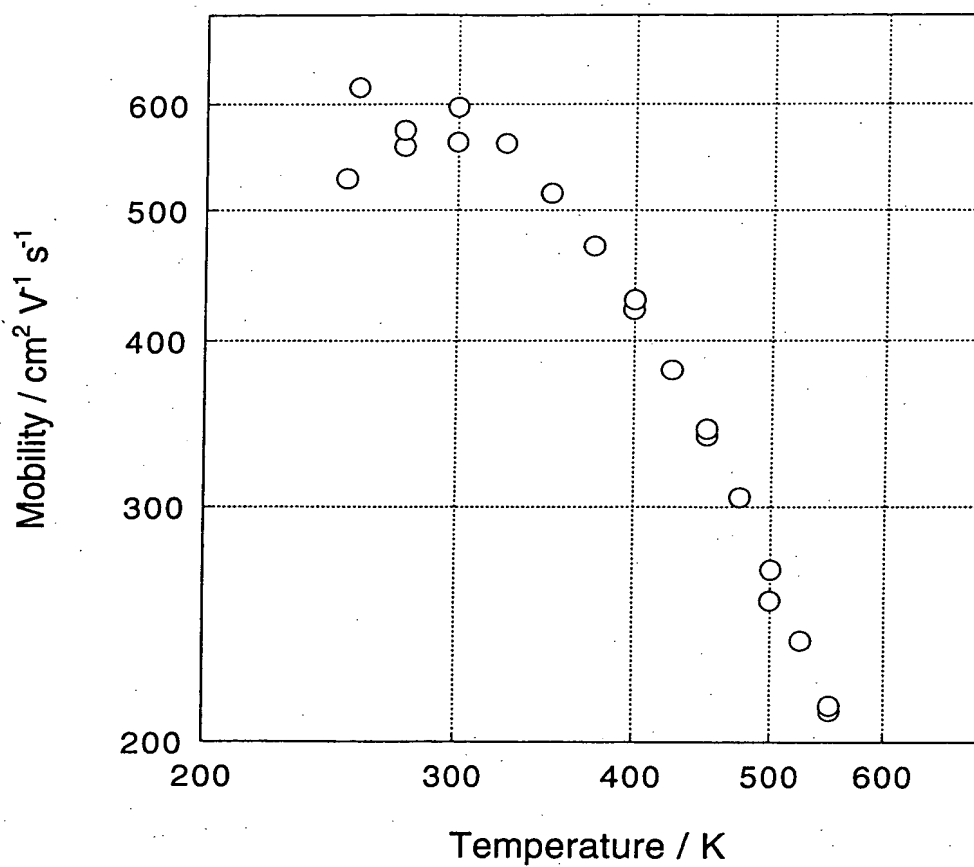


FIG. 7

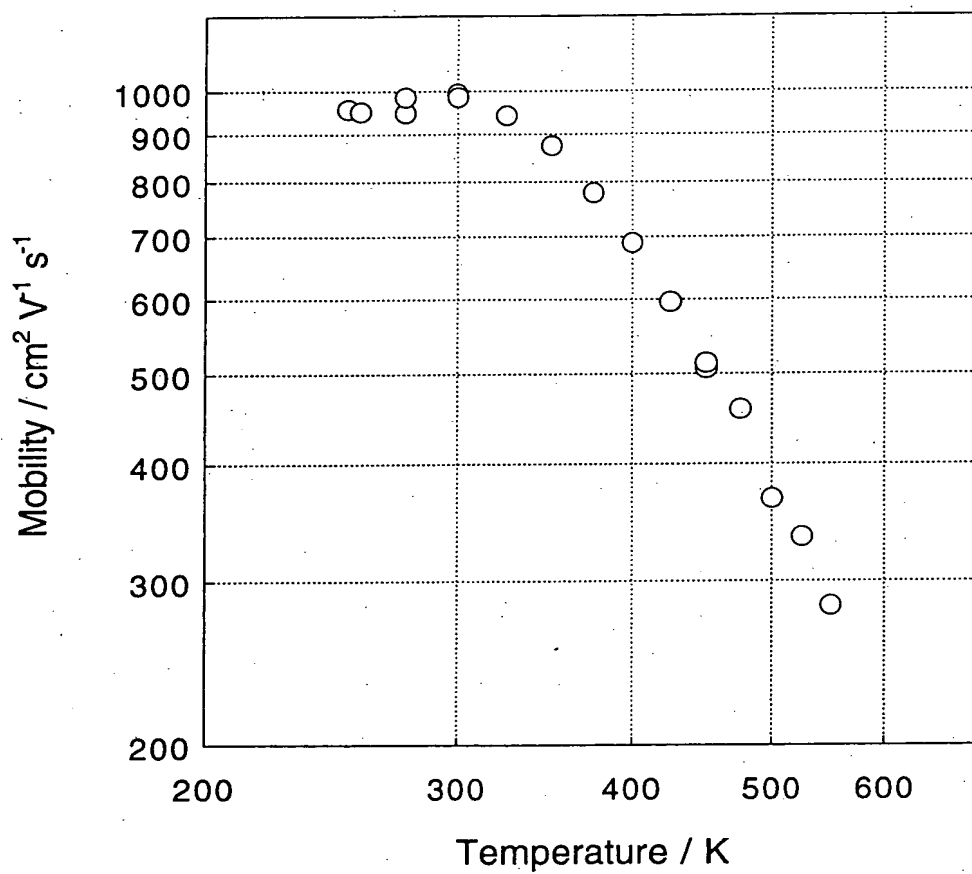


FIG. 8

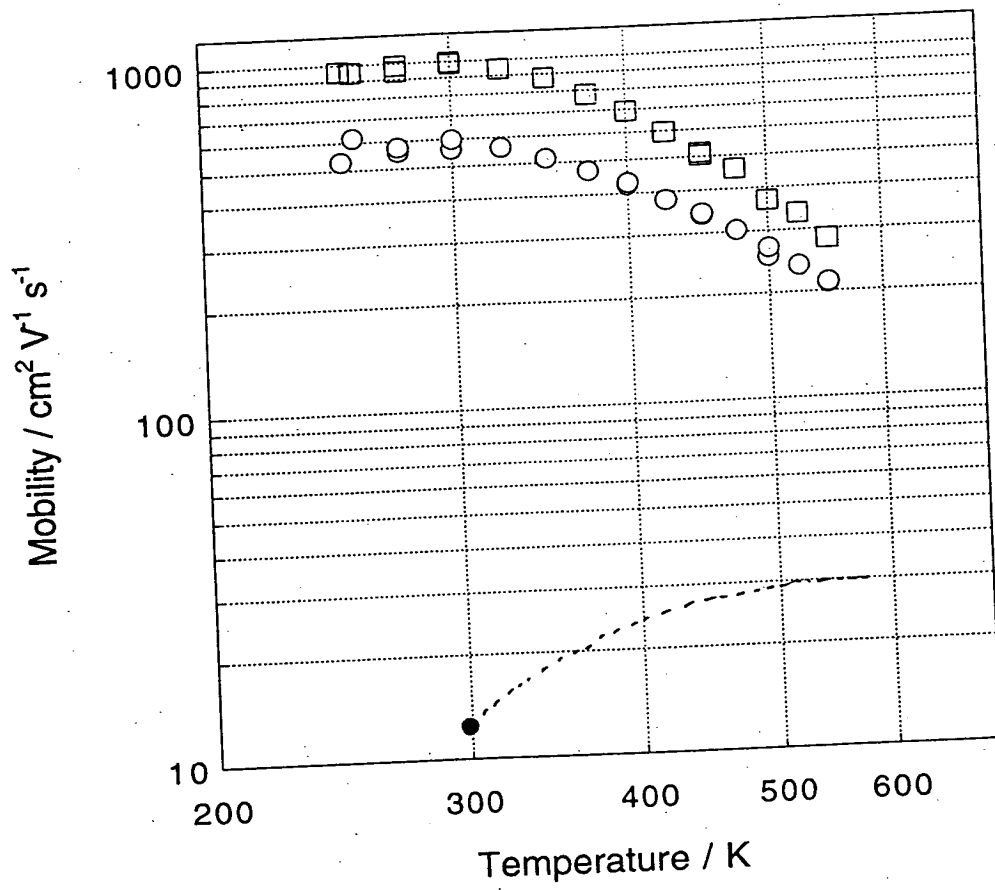


FIG. 9

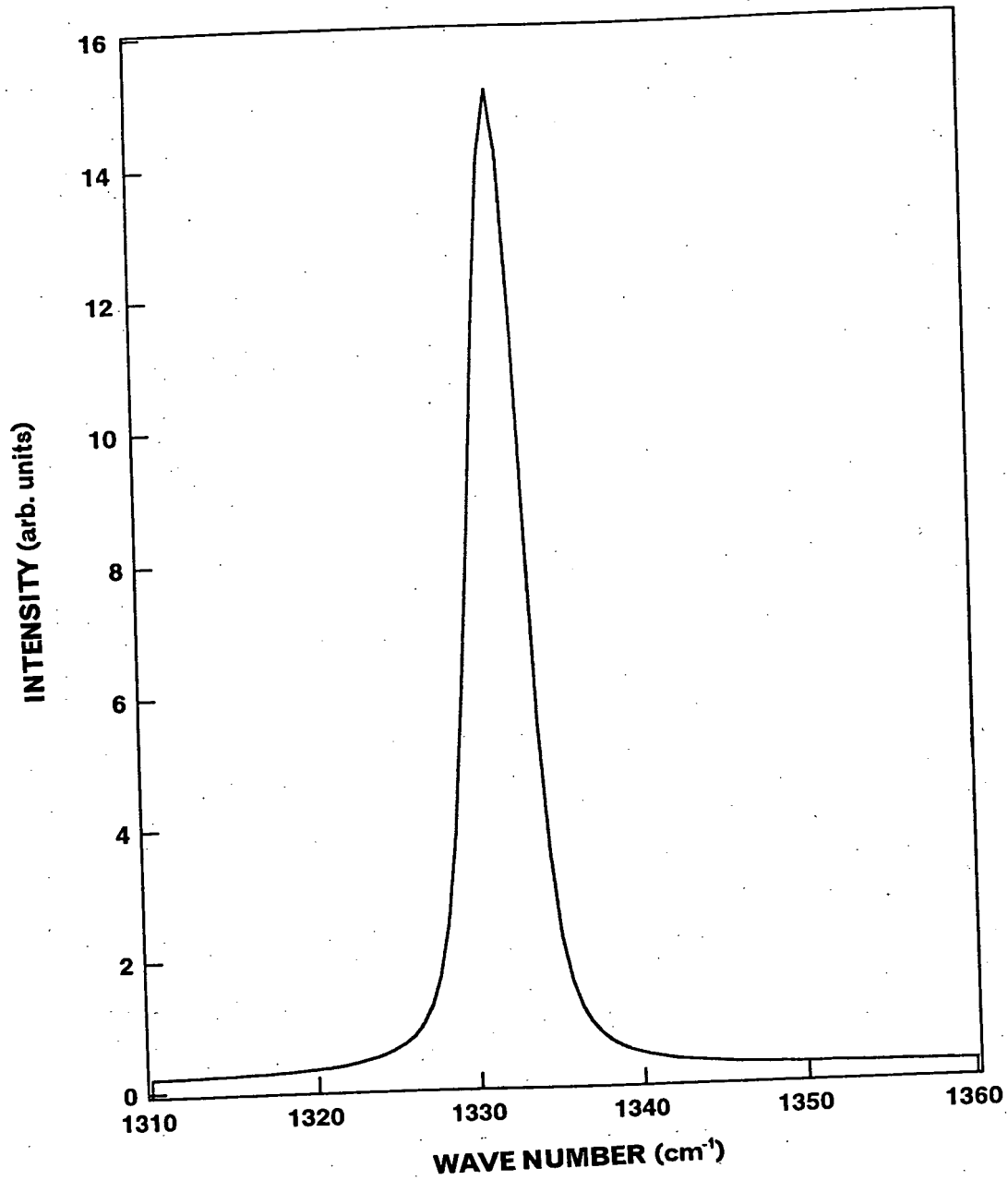


FIG. 10

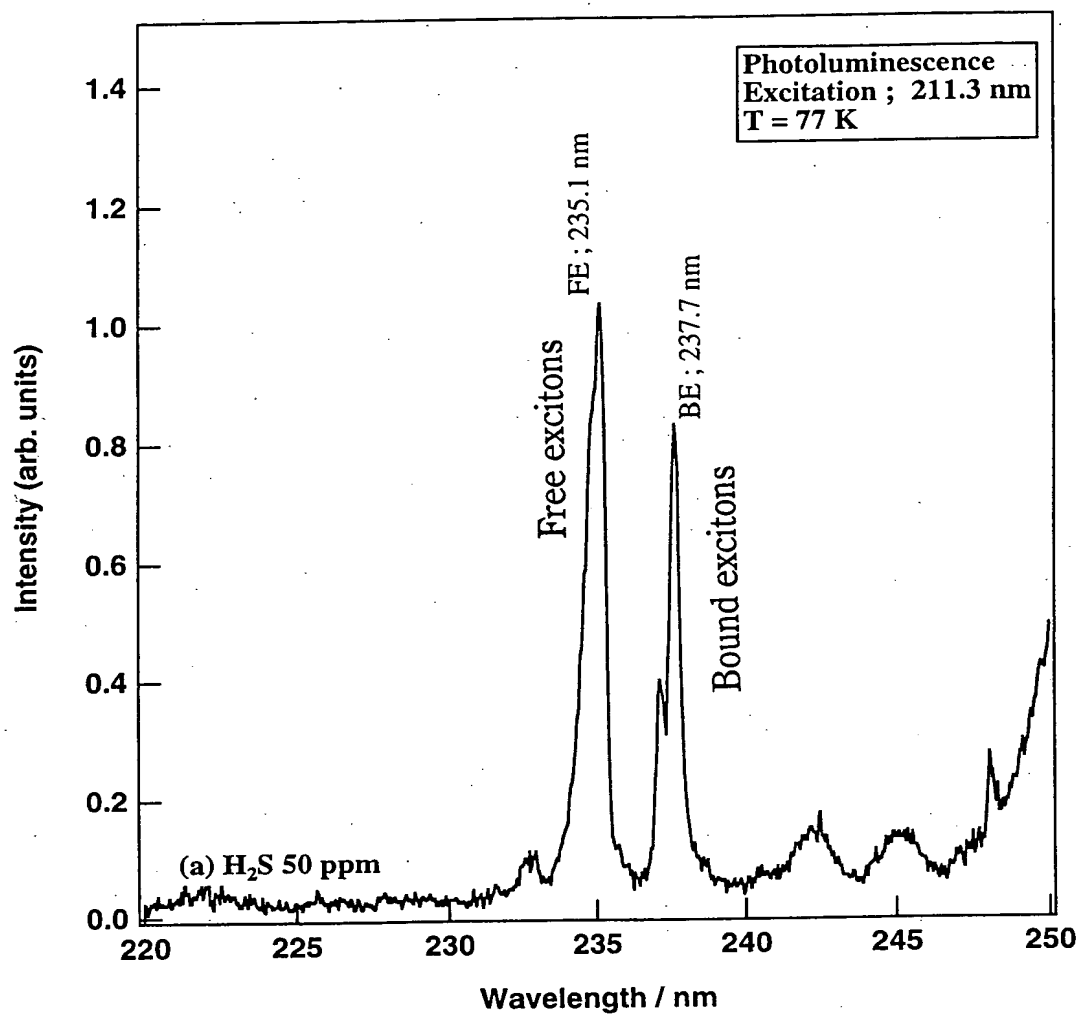


FIG. 11

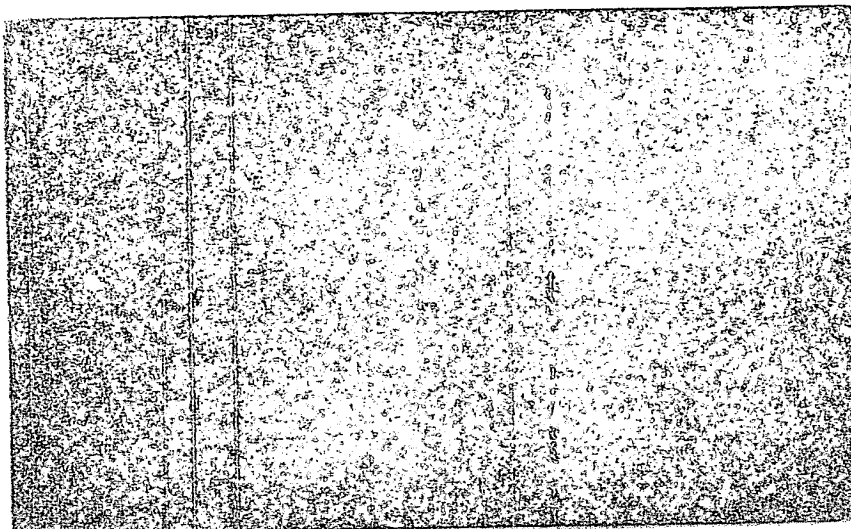


FIG. 12A

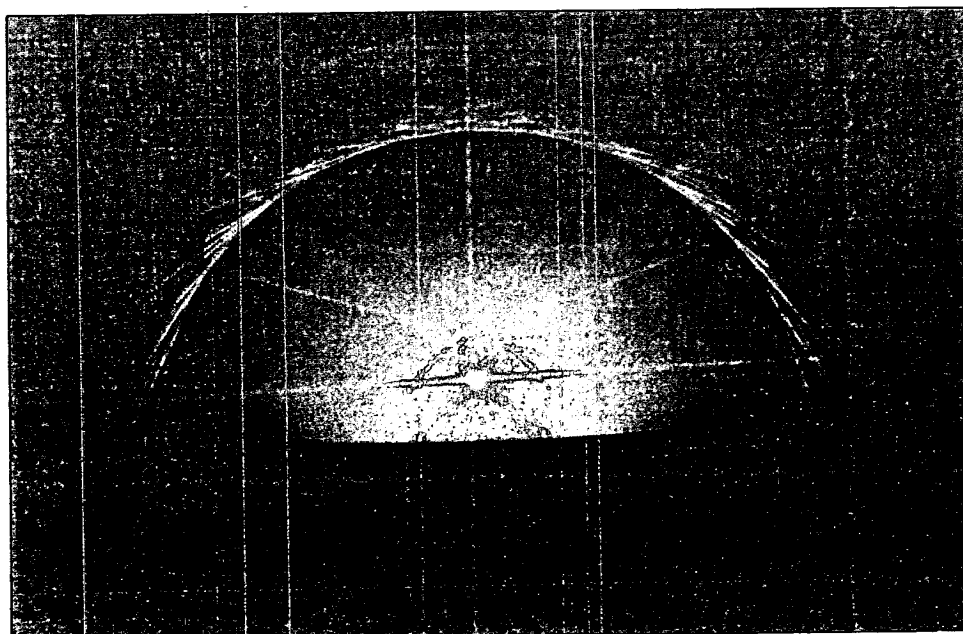


FIG. 12B

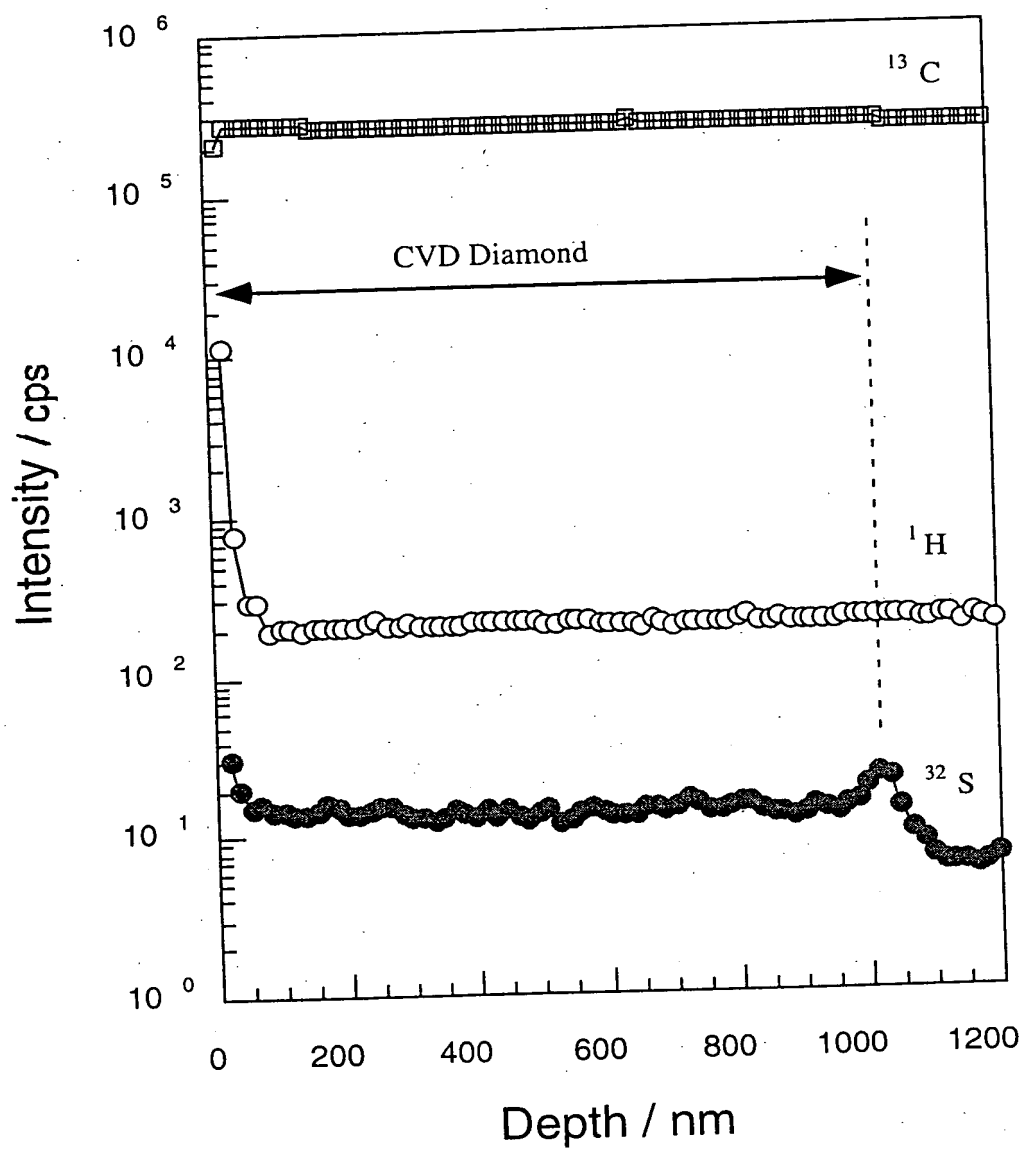


FIG. 13